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(54) Title: STABILIZATION OF SILSESQUIOXANE RESINS

(57) Abstract: Disclosed is silsesquioxane resin composition that contains a free radical curable functional group that is stabilized with a hydrophilic inhibitor. The hydrophilic inhibitor that has the capability to scavenge free radicals such as ascorbic acid or salicylic acid is used to stabilize the resin. The resins are useful in semiconductor formation such as for anti - reflective coatings, hardmasks or photoresist layers.



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